L Number	Hits	Search Text	DB	Time stamp
1	57	(((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas))) same (dimethyldichlorosilane me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3	USPAT; US-PGPUB;	2004/01/21 07:30
		near ?sub.2 near sicl?sub.2))	EPO; JPO; DERWENT	
2	2	((((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas))) same	USPAT;	2004/01/21 07:32
		(dimethyldichlorosilane me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3	US-PGPUB;	
		near ?sub.2 near sicl?sub.2))) same (substrate near glass)	EPO; JPO; DERWENT	
3	11	((((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas))) same	USPAT;	2004/01/21 07:59
	• •	(dimethyldichlorosilane me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3	US-PGPUB;	2001101121 07.39
		near ?sub.2 near sicl?sub.2))) and (substrate same glass)	EPO; JPO;	
			DERWENT	
4	9	(((((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas))) same	USPAT;	2004/01/21 07:32
		(dimethyldichlorosilane me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3	US-PGPUB;	
		near ?sub.2 near sicl?sub.2))) and (substrate same glass)) not (((((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas))) same	EPO; JPO; DERWENT	
		(dimethyldichlorosilane me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3	DERWENT	
		near ?sub.2 near sicl?sub.2))) same (substrate near glass))		
5	37	((((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas))) same	USPAT;	2004/01/21 07:59
		(dimethyldichlorosilane me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3	US-PGPUB;	
		near ?sub.2 near sic!?sub.2))) and (glass)	EPO; JPO;	
6	26	((((((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas))) same	DERWENT USPAT;	2004/01/21 08:08
U	20	((((stell stell sub.4 (smeon hear terractionale)) same (vapor gas))) same (dimethyldichlorosilane me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3	US-PGPUB;	2004/01/21 06.06
0.0		near ?sub.2 near sicl?sub.2))) and (glass)) not (((((sicl4 sicl?sub.4	EPO; JPO;	
		(silicon near tetrachloride)) same (vapor gas))) same	DERWENT	
		(dimethyldichlorosilane me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3		
		near ?sub.2 near sicl?sub.2))) same (substrate near glass)) (((((sicl4		
		sicl?sub.4 (silicon near tetrachloride)) same (vapor gas))) same (dimethyldichlorosilane me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3		
		near ?sub.2 near sicl?sub.2))) and (substrate same glass)))		
7	32	((crosslinked cured (cross near linked)) same (polydimethylsiloxane	USPAT;	2004/01/21 08:10
		dimethylpolysiloxane)) same ((silicon near (dioxide oxide)) siO siO2	US-PGPUB;	
		sio?sub.2) same (layer coating)	EPO; JPO;	
_			DERWENT	
8	13	(((crosslinked cured (cross near linked)) same (polydimethylsiloxane dimethylpolysiloxane)) same ((silicon near (dioxide oxide)) siO siO2	USPAT;	2004/01/21 08:10
		sio?sub.2) same (layer coating)) not ((((((sicl4 sicl?sub.4 (silicon near	US-PGPUB; EPO; JPO;	
		tetrachloride)) same (vapor gas))) same (dimethyldichlorosilane	DERWENT	
		me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3 near ?sub.2 near		
		sicl?sub.2))) same (substrate near glass)) "35")		
9	30	(((crosslinked cured (cross near linked)) same (polydimethylsiloxane	USPAT;	2004/01/21 08:10
		dimethylpolysiloxane)) same ((silicon near (dioxide oxide)) siO siO2	US-PGPUB;	
		sio?sub.2) same (layer coating)) not (((((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas))) same (dimethyldichlorosilane	EPO; JPO; DERWENT	
		me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3 near ?sub.2 near	DEKWENT	
		sicl?sub.2))) same (substrate near glass)) (((((sicl4 sicl?sub.4 (silicon near		
		tetrachloride)) same (vapor gas))) same (dimethyldichlorosilane		
		me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3 near ?sub.2 near		
		sicl?sub.2))) and (substrate same glass)) (((((sicl4 sicl?sub.4 (silicon near		!
		tetrachloride)) same (vapor gas))) same (dimethyldichlorosilane		
		me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3 near ?sub.2 near sicl?sub.2))) and (glass)))		*

10	20	((((crosslinked cured (cross near linked)) same (polydimethylsiloxane	USPAT;	2004/01/21 08:10
		dimethylpolysiloxane)) same ((silicon near (dioxide oxide)) siO siO2	US-PGPUB;	
		sio?sub.2) same (layer coating)) not ((((((sicl4 sicl?sub.4 (silicon near	EPO; JPO;	
		tetrachloride)) same (vapor gas))) same (dimethyldichlorosilane	DERWENT	
		me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3 near ?sub.2 near		
		sicl?sub.2))) same (substrate near glass)) (((((sicl4 sicl?sub.4 (silicon near		
1		tetrachloride)) same (vapor gas))) same (dimethyldichlorosilane		
		me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3 near ?sub.2 near		
		sicl?sub.2))) and (substrate same glass)) (((((sicl4 sicl?sub.4 (silicon near		
		tetrachloride)) same (vapor gas))) same (dimethyldichlorosilane		
		me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3 near ?sub.2 near		
		sicl?sub.2))) and (glass)))) and glass		